October 20 (Tue.), 2026

[Oral 05] AI & ML for CMP / Process Control

16:55-17:55

International Conference Hall (B1F)

● Session Chair: Chao-Cheng Arthur Chen (NTUST, Taiwan)

16:55-17:15 [Oral 05-1]	AI-Enabled CMP Process Optimization in Advanced Semiconductor Manufacturing	Cheng Zhongyao (Inst. for Infocomm Research (I2R), Singapore), Su Myat Noe, Leong Lup San, Chen Gim Guan (Inst. for Microelectronics (IME), Singapore), Qian Peisheng, Ata Kircali Sezin, Gopinathan Arjunan, Ashish James (Inst. for Infocomm Research (I2R),
17:15-17:35 [Oral 05-2]	Digital-Twin-Based Evaluation of Virtual Metrology Outputs for APC Decision Quality in CMP	Seungchoun Choi, Yonghwan Yim, and Semyeong Oh (Amously Inc., Korea)
17:35-17:55 [Oral 05-3]	Accelerating CMP Model Development Using Machine Learning for Early Manufacturability Risk Detection	Ushasree Katakamsetty (Globalfoundries Singapore Pte. Ltd., Singapore), Henning Turnow, Boris Vasilev (Globalfoundries Dresden, Germany), and Stefan Nikolaev Voykov (Globalfoundries, Bulgaria), Ruben Ghulghazaryan (Siemens Industry Software, Armenia), Dav